

ABSTRACT OF THE DISCLOSURE

In one embodiment, an electrostatic chuck includes a body having a top surface facing a wafer and a reflective coating over the top surface. The reflective coating is formed on areas of the top surface that do not contact a wafer so as to not appreciably  
5 affect the clamping function of the electrostatic chuck. The reflective coating helps raise the operating temperature of the wafer by reflecting heat radiated from the wafer back onto the wafer. In one embodiment, the reflective coating comprises a material that is relatively good in reflecting radiation in the infrared region.